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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/828,475	04/21/2004	Yoshihisa Dotta	1035-506	7094
23117	7590	05/19/2005	EXAMINER	
NIXON & VANDERHYE, PC			NADAV, ORI	
901 NORTH GLEBE ROAD, 11TH FLOOR			ART UNIT	PAPER NUMBER
ARLINGTON, VA 22203			2811	

DATE MAILED: 05/19/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

H'A

## Office Action Summary

Application No.	10/828,475	Applicant(s)	DOTTA ET AL
Examiner	ori nadav	Art Unit	2811

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --  
**Period for Reply**

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

### Status

1) Responsive to communication(s) filed on 11 April 2005.  
 2a) This action is **FINAL**.                            2b) This action is non-final.  
 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

### Disposition of Claims

4) Claim(s) 1-9 and 17-20 is/are pending in the application.  
 4a) Of the above claim(s) \_\_\_\_\_ is/are withdrawn from consideration.  
 5) Claim(s) \_\_\_\_\_ is/are allowed.  
 6) Claim(s) 1-9 and 17-20 is/are rejected.  
 7) Claim(s) \_\_\_\_\_ is/are objected to.  
 8) Claim(s) \_\_\_\_\_ are subject to restriction and/or election requirement.

### Application Papers

9) The specification is objected to by the Examiner.  
 10) The drawing(s) filed on \_\_\_\_\_ is/are: a) accepted or b) objected to by the Examiner.  
     · Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  
     · Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).  
 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

### Priority under 35 U.S.C. § 119

12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).  
 a) All    b) Some \* c) None of:  
 1. Certified copies of the priority documents have been received.  
 2. Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.  
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

\* See the attached detailed Office action for a list of the certified copies not received.

### Attachment(s)

1) <input type="checkbox"/> Notice of References Cited (PTO-892)	4) <input type="checkbox"/> Interview Summary (PTO-413)
2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/Mail Date. _____
3) <input type="checkbox"/> Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date _____	5) <input type="checkbox"/> Notice of Informal Patent Application (PTO-152)
	6) <input type="checkbox"/> Other: _____

## **DETAILED ACTION**

### ***Claim Objections***

Claim 20 is objected to because of the following informalities: Claim 20 recites the limitation "the aperture section of the electrode" in line 2. There is insufficient antecedent basis for this limitation in the claim. Appropriate correction is required.

### ***Claim Rejections - 35 USC § 112***

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claim 20 is rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention. The claimed limitations of the aperture section of the field oxide film is formed in the aperture section of the electrode, when pependicularly viewing the semiconductor substrate, as recited in claim 20, are unclear as to which element is the aperture section of the electrode.

### ***Claim Rejections - 35 USC § 103***

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-9 and 17-20 are rejected under 35 U.S.C. 103(a) as being unpatentable over Finnila (5,426,072).

Finnila teaches in figure 6 and related text a semiconductor apparatus, comprising:

    a semiconductor substrate 29, 11, 12;

    a field oxide film 13 formed in a surface of the semiconductor substrate, the field oxide film having an aperture section (the aperture section is the section between the most right FOX region and the middle FOX region);

    a penetration electrode 21 (the right electrode located between the two FOX regions) electrically connected to the electrode via the aperture section of the field oxide film and via a hole formed in the semiconductor substrate,

        the hole in the semiconductor substrate being formed entirely in the aperture section of the field oxide film, when perpendicularly viewing the semiconductor substrate , when perpendicularly viewing the semiconductor substrate, so that an opening of the hole is smaller than the aperture section,

        wherein the penetration electrode is formed in a field area of the surface of the semiconductor substrate,

        wherein an insulating film 15 (see figure 4) is formed on an internal surface of the hole, between the internal surface of the hole and a sidewall of the penetration electrode,

        wherein the penetration electrode includes an electrically conductive film 16 on the insulating film that is formed on the internal surface of the hole,

wherein the penetration electrode includes a hole-filling section formed in the hole,

wherein the hole-filling section is made of an insulating material and of an electrically conductive material.

Finnila does not teach in figure 6 a pad electrode formed on the field oxide film. Finnila teaches in figure 8 and related text a pad electrode 46, 48 connecting electrode 23 to an external wirebond. Therefore, Finnila teaches in figure 8 a pad electrode 46, 48 formed on the field oxide film.

It would have been obvious to a person of ordinary skill in the art at the time the invention was made to form pad electrode 46, 48 on the field oxide film in Finnila's structure of figure 6 in order to use the device in an practical application.

Note that the broad recitation of the claim does not require the pad electrode to be formed directly on the field oxide film.

Regarding claims 3 and 4, Finnila teaches a pad electrode 46, 48 has an aperture section and the penetration electrode electrically connected to the pad electrode, wherein the pad electrode has an aperture section, wherein the aperture section of the field oxide film is formed in the aperture section of the electrode, when perpendicularly viewing the semiconductor substrate.

Regarding claim 17, Finnila teaches a pad electrode formed so that there is no overlap with the hole when pependicularly viewing the semiconductor substrate.

***Response to Arguments***

Applicant's arguments with respect to claims 1-9 and 17-20 have been considered but are moot in view of the new ground(s) of rejection.

***Conclusion***

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

**Papers related to this application may be submitted to Technology center (TC) 2800 by facsimile transmission. Papers should be faxed to TC 2800 via the TC 2800 Fax center located in Crystal Plaza 4, room 4-C23. The faxing of such**

**papers must conform with the notice published in the Official Gazette, 1096 OG 30 (November 15, 1989). The Group 2811 Fax Center number is (703) 308-7722 and 308-7724. The Group 2811 Fax Center is to be used only for papers related to Group 2811 applications.**

Any inquiry concerning this communication or any earlier communication from the Examiner should be directed to *Examiner Nadav* whose telephone number is **(571) 272-1660**. The Examiner is in the Office generally between the hours of 7 AM to 4 PM (Eastern Standard Time) Monday through Friday.

Any inquiry of a general nature or relating to the status of this application should be directed to the **Technology Center Receptionists** whose telephone number is **308-0956**



O.N.  
5/13/05

ORI NADAV  
PRIMARY EXAMINER  
TECHNOLOGY CENTER 2800